Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	15843	polymer and residue and etch$	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 08:03
L3	7889	l2 and oxygen	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 08:03
L4	3232	l3 and oxidation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 08:03
L5	2019	l4 and oxidiz$	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 08:03
L6	404	l5 and sidewall	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 09:01
L7	35190	etch$ adj3 metal	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 09:01
L8	7890	polymer adj3 residue	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 09:01
L9	285	l7 and l8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/26 09:01

| L10 | 183 | I9 and oxygen | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/26 09:02 |